

Title (en)

DEVICE AND METHOD FOR THE INTERFEROMETRIC MEASUREMENT OF PHASE MASKS

Title (de)

VORRICHTUNG UND VERFAHREN ZUR INTERFEROMETRISCHEN MESSUNG VON PHASENMASKEN

Title (fr)

DISPOSITIF ET PROCEDE DE MESURE INTERFEROMETRIQUE DE MASQUES DE PHASES

Publication

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Application

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Priority

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Abstract (en)

[origin: DE102005041203A1] A phase mask (4), positionable in X-Y direction, is arranged between and close to the pupil levels of two aligned imaging lenses (2). A coherency mask (1) and a diffraction grating (3) are arranged over the imaging lenses. By translational shifting of the coherence mask and/or the diffraction grating in X-Y direction, a phase shifting interferogram is produced and is imaged over the phase mask by another imaging lens (5) on a spatial light detector (6). Phase and transmission function of the phase mask are evaluated.

IPC 8 full level

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